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ABSTRACT

An optical property measurement apparatus (90) is equipped with an optical system unit (93) that selectively
5 places an opening section (97) for passing illumination light, a microlens array (98) for measuring wavefront aberration, and a polarization detection system (99) for measuring a polarization state of the illumination light on an optical path of the illumination light. Accordingly an illumination
10 shape and a size of an illumination optical system, wavefront aberration of a projection optical system and a polarization state of the illumination light can be measured together. Therefore, for example, even when exposure is performed with polarized illumination that is a type of modified illumination,
15 highly-accurate exposure can be achieved by adjusting various optical systems based on the measurement results.

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